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U.S.S.N. 10,791,247

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Specification Amendments

Please amend paragraph 0030 as follows:

[0030] After the substrate 32 is placed on the substrate support 30 and the cleaning fluid 14 is provided in the cleaning fluid holding tank 12, the cleaning chamber 28 is set at the temperature and pressure conditions that are required to transform the cleaning fluid 14 from the liquid or gaseous state (non-supercritical state) to the supercritical fluid state, and these threshold temperature and pressure conditions vary according to the cleaning fluid used, as shown in Table I. By operation of the pump 18, the cleaning fluid 14 is then pumped from the cleaning fluid holding tank 12, through the holding tank outlet conduit 16 and into the mixing conduit 20. Simultaneously, by operation of the pump 24, the solvent 23 is distributed from the solvent holding tank 22 and into the mixing conduit 20. As they are pumped through the mixing conduit 20, the cleaning fluid 14 and the solvent 23 mix together to define a cleaning fluid/solvent mixture 26 that enters the cleaning chamber 28.